

What is claimed is:

1. A cleaning method of treatment equipment, comprising:  
a step of, while supplying a cleaning gas containing a  
substance directly complexing prescribed metal in a treatment  
5 chamber of the treatment equipment that treats a substrate,  
exhausting the cleaning gas from the treatment chamber.

2. The cleaning method of claim 1:

wherein the substance of directly complexing is carboxylic  
acid or a derivative of carboxylic acid.

10 3. The cleaning method of claim 2:

wherein the carboxylic acid or the derivative of carboxylic  
acid is a substance expressed by the following equations:  $\text{RCOOH}$ ,  
 $\text{RCOOR}'$ , or  $\text{R}(\text{COOH})_n$  ( $\text{R}$ ,  $\text{R}'$  are hydrocarbon group capable of  
containing halogen atom,  $n$  being an integer).

15 4. The cleaning method of claim 3:

wherein the substance for directly complexing is  
trifluoroacetic acid.

5. The cleaning method of claim 1:

wherein the treatment equipment is film formation  
20 equipment.

6. The cleaning method of claim 1:

wherein the prescribed metal is copper.

7. The cleaning method of claim 1:

wherein the cleaning gas contains an additive that promotes  
25 complexing of the prescribed metal.

8. The cleaning method of claim 1:

wherein the additive is water vapor.

9. A cleaning method of treatment equipment, comprising

the steps of:

supplying, in a treatment chamber of treatment equipment treating a substrate, a cleaning gas containing a substance directly complexing prescribed metal; and

5 exhausting the cleaning gas from the treatment chamber.

10. The cleaning method of claim 9:

wherein the steps of supplying the cleaning gas and of exhausting the cleaning gas are alternately repeated.

11. Treatment equipment, comprising:

10 a treatment chamber for treating a substrate;

a susceptor disposed in the treatment chamber and on which the substrate is disposed;

a treatment gas supply system for supplying, in the treatment chamber, a treatment gas containing copper as a  
15 component;

an evacuation system for evacuating the inside of the treatment chamber; and

a TFA supply system for supplying trifluoroacetic acid in the treatment chamber.

20 12. The treatment equipment of claim 11:

wherein the treatment gas supply system comprises a treatment agent tank, treatment gas supply piping connecting the treatment chamber and the treatment agent tank and a treatment agent vaporizer disposed in the middle of the treatment gas supply  
25 piping;

wherein the TFA supply system comprises a TFA tank and a TFA supply piping connecting the TFA tank and the treatment gas supply piping, the treatment gas supply piping being downstream

the treatment agent vaporizer in a direction of treatment gas movement.

13. The treatment equipment of claim 12:

5 wherein at least in a portion downstream the vaporizer of the treatment agent supply piping a heater is disposed.

14. The treatment equipment of claim 13:

wherein the treatment chamber is furnished with a heater to heat a wall surface of the treatment chamber.

15. The treatment equipment of claim 12:

10 wherein the treatment agent tank is a tank containing a treatment agent containing copper as a component.

16. The treatment equipment of claim 11, further comprising:

15 a supply system for supplying an additive that promotes complexing of copper.